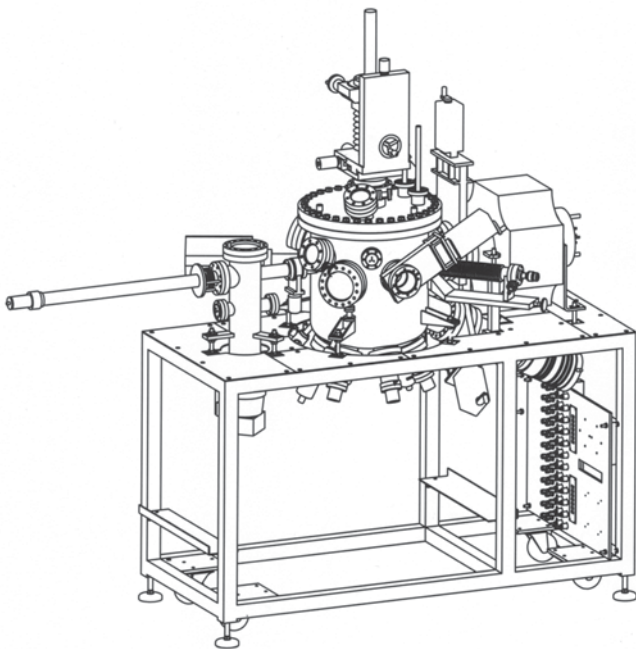


RESEARCH MBD-SYSTEM RS-2

*Modular, expandable
Ready-for-use*



Complete MBD System for the preparation of epitaxial films (semiconductors, metals, dielectrics and organics) on 1" or 2" wafers for various scientific applications.

- UHV-compatible (achievable base pressure better than 5×10^{-11} mbar in the growth chamber)
- High precision and high quality standard (Made in Germany)
- Easy-to-handle
- State-of-the-art technology (substrate temperature and film thickness uniformities better than $\pm 1\%$)
- Ready for use after installation on site

Description of the RS-2

The system is based on two chambers: a growth chamber and a load-lock chamber with the possibility to mount additional chambers.

Growth chamber:

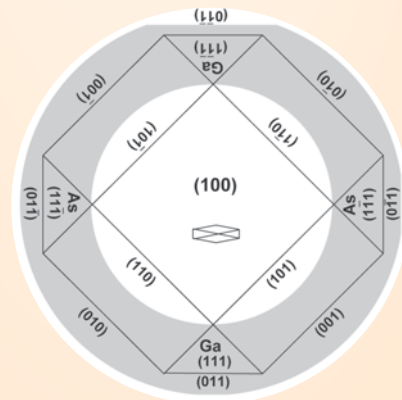
- 16" chamber made from stainless steel
- With 6 cell ports
- Equipped with 4 effusion cells including water cooling and shutter dependent on the material system which will be prepared
- Equipped with a manipulator for 1" or 2" wafer holders heatable up to 800 °C
- Cooling shroud in the area of the substrate
- Ion getter pump with booster

Load-lock chamber:

- Sample transfer
- Loading door
- Turbo molecular pump with roughing pump

Miscellaneous:

- With cabinet including all needed controllers
- Complete bake-out system
- Mounted on a stable rack
- Expandable with further UHV-equipment (e.g. analysis chambers for STM, AFM, UPS, XPS, KERR, LEED, etc.)



Surface orientation of GaAs(100)-wafer



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